

ABSTRACT

5 Provided is a method for producing a decomposing/cleaning composition which improves etching speed retention. A method for producing a decomposing/cleaning composition which contains (A) an N-substituted amide compound in which a hydrogen atom is not directly bonded to a nitrogen atom and (B) a quaternary alkyl ammonium fluoride or a hydrate thereof, said method having a preparation step for mixing the (A) and (B) components in an inert gas atmosphere.